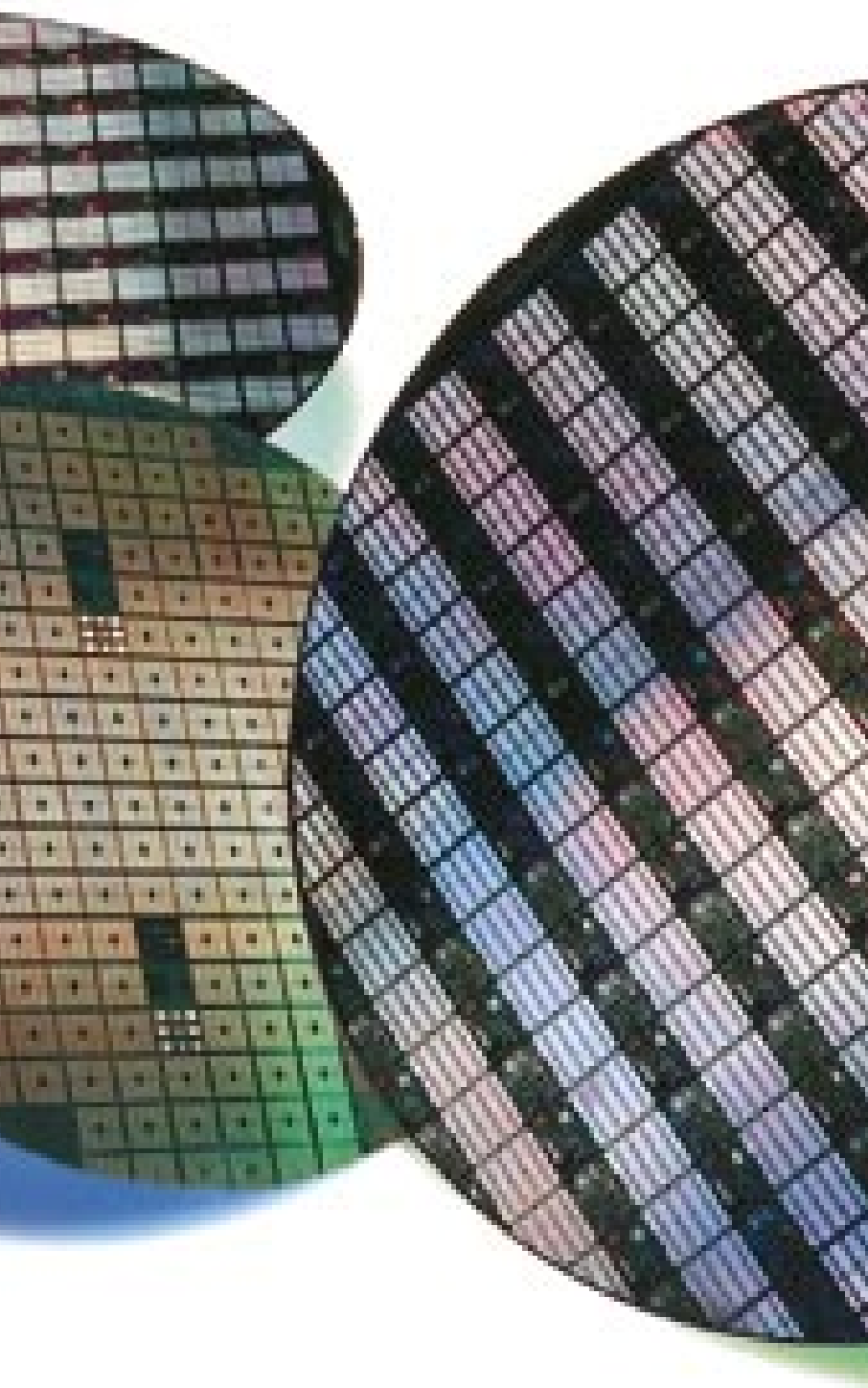


# Positive DUV Photoresist UV110™ Series



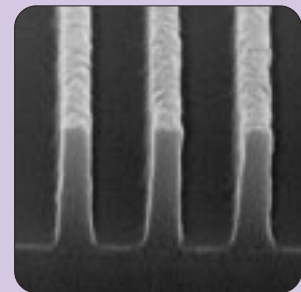
Advanced Resists for 130 nm Design Rules



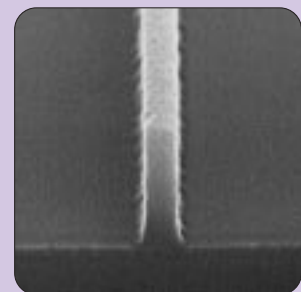
UV110 Series photoresists are multi-functional, DUV photoresists designed for 130 and 150 nm applications.

#### Features include:

- Large process windows, including DOF:
  - $\geq 1.0 \mu\text{m}$  @ 150 nm 1:1.5 lines/spaces
  - $\geq 0.6 \mu\text{m}$  @ 150 nm isolated lines
  - $\geq 1.0 \mu\text{m}$  @ 150 nm 1:1 lines/spaces
- Maximum isolated line film retention to  $< 110 \text{ nm}$
- Excellent CD uniformity of  $< 9 \text{ nm}$  @ 140 nm 1:2 lines/spaces



1:1.5 Lines/Spaces @ 130 nm



Isolated Line @ 130 nm

UV110 0.60 NA, AR3™

Contact your local Shipley representative for more information on these and other Shipley products.

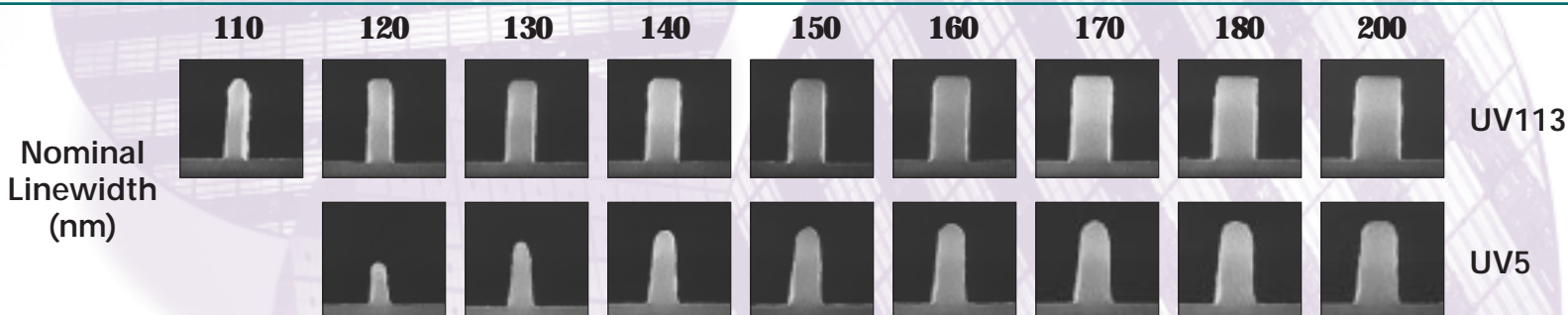
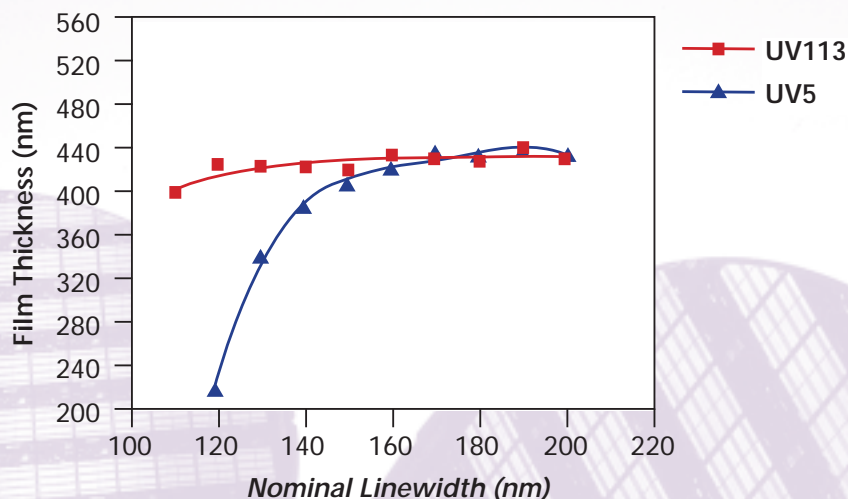


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# Positive DUV Photoresist UV110 Series

DUV

## Isolated Line Film Retention



## CD Uniformity

